

A CHEMICAL VAPOR DEPOSITION (CVD) APPARATUS USABLE IN THE  
MANUFACTURE OF SUPERCONDUCTING CONDUCTORS

5 ABSTRACT OF INVENTION

A chemical vapor deposition (CVD) apparatus usable in the manufacture of a superconducting conductor on an elongate substrate is disclosed. The CVD apparatus includes a reactor, at least one substrate heater, and at least one precursor injector having a longitudinal  
10 flow distributor. Optionally, the CVD apparatus may include one of a transverse lateral flow restrictor, a shield for protecting a low-temperature region of the substrate, and both.

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